ELECTRONIC GAS

PLASMA ETCHING MIXTURE 02/CF4

Carbon Tetrafluoride can be mixed with oxygen in order to provide concentration of less than 100%. Using Carbon Tetrafluoride in this form is used for plasma cleaning of CVD reactors. Carbon Tetrafluoride / oxygen mixtures are prepared as ordered. Concentrations other than those listed below are available upon request.

Container Information

CYLINDER CONNECTION: std: CGA-880 ($0_2 < 5\%$) / CGA-590 ($0_2 > 5\%$) DOPING CONCENTRATIONS can be mixed with UHP or VLSI grade balance gases

Oxygen	Cylinder	Pressure	Content	
Concentration	Size	psig @ 70°F	ft ³	m ³
4%	044	500	61.5	1.74
	016	500	24	0.68
8.5%	044	500	62	1.74
LFE-DE-100	016	500	24	0.68
17.5%	044	500	62	1.74
LFE-DE-100	016	500	24	0.68
92%	044	500	60	1.57
LFE-DE-180	016	500	22	0.60
97%	044	500	60	1.57
LFE-DE-180	016	500	22	0.60
SHELF LIFE: 1 year				

DOT Shipping Information

	CARBON TETRAFLU	ARBON TETRAFLUORIDE BALANCE					
	Oxygen Conc	Shipping Name	Shipping Papers	Shipping Labels			
	4%	4% Oxygen/Carbon Tetrafluoride Mixture	Compressed Gases, Non-flammable, nos (4% Oxygen/Carbon Tetrafluoride Mixture) 2.2 UN 1956	Non-flammable Gas			
	8%	8% Oxygen/Carbon Tetrafluoride Mixture	Compressed Gases, Non-flammable, nos (8% Oxygen/Carbon Tetrafluoride Mixture) 2.2 UN 1956	Non-flammable Gas			
	10%	10% Oxygen/Carbon Tetrafluoride Mixture	Compressed Gases, Non-flammable, nos (10% Oxygen/Carbon Tetrafluoride Mixture) 2.2 UN 1956	Non-flammable Gas			
	20%	20% Oxygen/Carbon Tetrafluoride Mixture	Compressed Gases, Non-flammable, nos (20% Oxygen/Carbon Tetrafluoride Mixture) 2.2 UN 1956	Non-flammable Gas			